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MRAM device according to example embodiments. The memory controller 320 may provide a control signal for controlling the memory 310.

The MRAM device according to example embodiments may be used in various types of electronic devices, e.g., 5 mobile devices, memory cards, computers, etc.

Referring to FIG. 23, an electronic device 2300 including a semiconductor device according to example embodiments disclosed herein may be used in, but not limited to, a computing device, a personal digital assistant (PDA), a 10 laptop computer, a mobile computer, a web tablet, a wireless phone, a cell phone, a smart phone, a digital music player, or a wireline or wireless electronic device. The electronic device 2300 may include a controller 2310, an input/output device 2320 such as, but not limited to, a keypad, a key- 15 board, a display, or a touch-screen display, a memory 2330, and a wireless interface 2340 that are combined to each other through a bus 2350. The controller 2310 may include, for example, at least one microprocessor, a digital signal process, a microcontroller or the like. The memory 2330 may be 20 configured to store a command code to be used by the controller 2310 or a user data. The memory 2330 may include a semiconductor device according to example embodiments of the inventive concept. The electronic device 2300 may use a wireless interface 2340 configured to 25 transmit data to or receive data from a wireless communication network using a RF signal. The wireless interface 2340 may include, for example, an antenna, a wireless transceiver and so on. The electronic system 2300 may be used in a communication interface protocol of a communi- 30 cation system, such as, but not limited to, Code Division Multiple Access (CDMA), Global System for Mobile Communications (GSM), North American Digital Communications (NADC), Extended Time Division Multiple Access (E-TDMA), Wideband CDMA (WCDMA), CDMA2000, 35 Wi-Fi, Municipal Wi-Fi (Muni Wi-Fi), Bluetooth, Digital Enhanced Cordless Telecommunications (DECT), Wireless Universal Serial Bus (Wireless USB), Fast low-latency access with seamless handoff Orthogonal Frequency Division Multiplexing (Flash-OFDM), IEEE 802.20, General 40 Packet Radio Service (GPRS), iBurst, Wireless Broadband (WiBro), WiMAX, WiMAX-Advanced, Universal Mobile Telecommunication Service-Time Division Duplex (UMTS-TDD), High Speed Packet Access (HSPA), Evolution Data Optimized (EVDO), Long Term Evolution-Advanced (LTE- 45 Advanced), Multichannel Multipoint Distribution Service (MMDS), and so forth.

Referring to FIG. 24, a memory system including a semiconductor device according to example embodiments disclosed herein will be described. The memory system 50 2400 may include a memory device 2410 for storing large amounts of data and a memory controller 2420. The memory controller 2420 controls the memory device 2410 to read data stored in the memory device 2410 or to write data into the memory device 2410 in response to a read/write request 55 of a host 2430. The memory controller 2430 may include an address-mapping table for mapping an address provided from the host 2430 (e.g., a mobile device or a computer system) into a physical address of the memory device 2410. The memory device 2410 may be a semiconductor device 60 according to example embodiments disclosed herein.

The semiconductor memory devices disclosed herein may be encapsulated using various and diverse packaging techniques. For example, the semiconductor memory devices according to the aforementioned example embodiments may be encapsulated using any one of a package on package (POP) technique, a ball grid arrays (BGAs) technique, a chip

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scale packages (CSPs) technique, a plastic leaded chip carrier (PLCC) technique, a plastic dual in-line package (PDIP) technique, a die in waffle pack technique, a die in wafer form technique, a chip on board (COB) technique, a ceramic dual in-line package (CERDIP) technique, a plastic quad flat package (PQFP) technique, a thin quad flat package (TQFP) technique, a small outline package (SOIC) technique, a shrink small outline package (SSOP) technique, a thin small outline package (TSOP) technique, a thin quad flat package (TQFP) technique, a system in package (SIP) technique, a multi-chip package (MCP) technique, a waferlevel fabricated package (WFP) technique and a wafer-level processed stack package (WSP) technique. The package in which the semiconductor memory device according to one of the above example embodiments is mounted may further include at least one semiconductor device (e.g., a controller and/or a logic device) that controls the semiconductor memory device. Additionally, the semiconductor memory devices disclosed herein may be part of a System on a Chip

What is claimed is:

- 1. A magnetoresistive random access memory device, comprising:
 - a first insulating interlayer on a first region and a second region of a substrate, the first insulating region comprising a flat first upper surface;
 - a pattern structure comprising magnetic tunnel junction (MTJ) structures and a filling layer pattern between the MTJ structures on the first insulating interlayer over the first region, the pattern structure comprising a flat second upper surface higher than the first upper surface, and the MTJ structures comprising a pillar shape;
 - bit lines on the pattern structure, and each of the bit lines contacting top surfaces of the MTJ structures;
 - a capping layer pattern on a sidewall of each of the MTJ structures and the first insulating interlayer between the MTJ structures on the first region; and
 - an etch-stop layer on the pattern structure between the bit lines on the first region and the first upper surface of the first insulating interlayer on the second region, a first portion of an upper surface of the etch-stop layer on the first region being higher than a second portion of the upper surface of the etch-stop layer on the second region.
- 2. The device of claim 1, wherein the capping layer pattern comprises silicon nitride or silicon oxynitride.
- 3. The device of claim 1, wherein the etch-stop layer is formed on the entire first upper surface of the first insulating interlayer on the second region, a sidewall of the filling layer at an interface between the first and second regions, and a portion of an upper surface of the filling layer.
- 4. The device of claim 1, wherein the etch-stop layer comprises silicon nitride, silicon oxynitride or aluminum oxide.
- 5. The device of claim 1, further comprising a second insulating interlayer on the etch-stop layer on the first and second regions, the second insulating interlayer filling gaps between the bit lines.
- **6**. The device of claim **1**, wherein the magnetoresistive random access memory device is part of a smartphone.
- 7. The device of claim 6, the smartphone comprises a touch-screen display.
- **8**. The device of claim **1**, further comprising a plurality of contact plugs, the contact plugs extending through the first insulating interlayer, wherein the contact plugs are electrically connected to the MTJ structures and the first region of the substrate.